



ACT Node Standard Recipes

Resist	PMMA	Sample Prep for Resist spin	
Tone	Positive Tone Resist	Cleaning Solution	Sonicate
Solid content	950k A4, 495k A2	Acetone	2~5 min
Developer	MIBK:IPA::1:3	IPA	2~5 min
Stopper	ISO-Propanol	Ethanol (optional)	2~5 min
Remover	Acetone	DI Water Rinse	2~5 min
Thinner	Anisole	Bake (Hotplate)	5 min

For Single Layer			
Spin	Speed		Time
950k	500 rpm		5 s
	3000rpm		45 s
Prebake	180 °C	if Hot Plate used	90s
For Bi-layer			
495k	500 rpm		5 s
	3000rpm		45 s
Prebake	180 °C	if Hot Plate used	90s
950k	500 rpm		5 s
	3000rpm		45 s
Prebake	180 °C	if Hot Plate used	90s
Exposure	Voltage	Base Dose	
	20kV	100 ~ 400 (uC(/cm2)	
Developer	MIBK:IPA::1:3	Dipping	1 min
Stopper	IPA	Dipping	30 ~ 60 s
Rinse	DI water	De-Ionised Water	30 s
Post Bake before etch (if required)	100 °C	Hot Plate	90 s
Remover	Acetone	Time depends on the patterns and thickness of resist	Soak for 30 ~ 40 min
Rinse		DI Water rinse	1 min

Created by: Gayatri Vaidya

Last Modified: 09/07/2020